

FORM PTO-1449	US Dept. of Commerce Patent and Trademark Office	ATTORNEY DOCKET NO.	SERIAL NO.
JUL 02 2004 INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		ATMI-668	10/792,038
		APPLICANT	
		Melissa K. Rath, et al.	
		FILING DATE	GROUP
		March 3, 2004	1756

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Le	AA	6,276,372	8/21/2001	Lee	134	1.3	
Le	AB	6,242,400	6/5/2001	Lee	510	176	
Le	AC	6,110,881	8/29/2000	Lee	510	175	
Le	AD	5,709,756	1/20/1998	Ward, et al.	134	1.3	
Le	AE	5,419,779	5/30/1995	Ward	134	38	
Le	AF	20020128164	9/12/2002	Hara, Yasushi ; et al.	510	175	11/30/2001
Le	AG	6,329,118	12/11/2001	Hussein, et al.	430	270.1	
Le	AH	10/389,214		Minsek, et al.	430	320	3/14/2003

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLAS S	TRANSLATION YES	NO
							X (abstract only)	

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)

Le	AI	Ito, "Dissolution Behavior of Chemically Amplified Resist Polymers for 248, 193-and 157 -nm Lithography, IBM J. Res. & Dev., Vol. 45 No. 5, (Sept. 2001)
Le	AJ	M. Hussein, et al. "A Novel Approach to Dual Damascene Patterning", Intel Corporation, Portland Technology Development, Hillsboro, OR

Continue on Page

EXAMINER <i>Hoai Van Le</i>	DATE CONSIDERED <i>25 May 2005</i>
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.	